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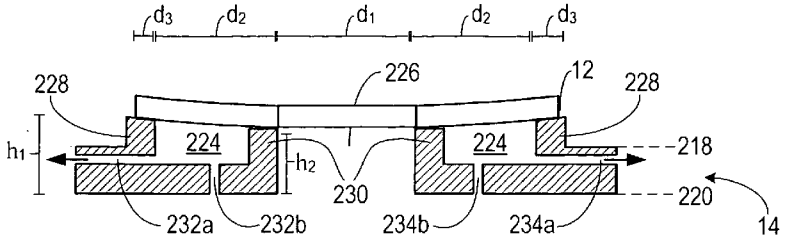


FIG. 20

(57) Abstract: System, method and process for imprinting a substrate using controlled deformation of a substrate and/or a template. The substrate and/or template may be positioned in single wave formation or double wave formation during an imprint lithography process.

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